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·VN	AA 5,612,574		3/18/97	Summerfelt et al.		•					
	AB	5,719,333		2/17/98	Hosoi et al.				,		
	AC	5,831,	333	11/3/98	Malladi et al.						
	AD	5,919,	548	7/6/99	Barron et al.	·······					
	AE	5,551,3	283	9/3/96	Manaka et al.						
	AF	5,492,0	011	2/20/96	Amano et al.						
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	**		"NTC and PTC Thermist	ose" ; http://www.chermedico.com/ntepte.lstml; 1/7/98; 3 pages.							
	AR		- "DI SB35 Linearized 4 V	Vire RTD Input";	; http://www.dataq.com/disb35.html; 1/7/98;	<del>3 pages.</del>					
	AS		"RTD"; http://www.mtis	ensors.com/rtdc.la	<u>hnl; 1/7/08; 3 pages</u> .						
	AT		"Low Cost Thermal Ribi	on (TM) uses thi	n film RTD": http://www.minco.com/c17624s	ur.html; 1/7/08; 1-page.					
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	AU		"Silicon Processing for 1	ve VLSI Em"; Ve	hume 1 Process Technology, Second Edition	; S. Welf et el.; 2000; ppo 22	25 and pps. 84	<del>-645</del> . ————			
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		AB	3,614,345	10/19/71	Quinn						
		AC	3,683,306	8/8/72	Bulthius et al.						
		AD	4,332,081	6/1/82	Francis			1			
		ΑE	4,518,944	5/21/85	Faris			ſ			
		AF	4,703,555	11/3/87	Hubner						
		AG	5,141,334	8/25/92	Castles						
		AH	5,347,869	9/20/94	Shie et al.						
		Al	5,406,109	4/11/95	Whitney						
		AJ	5,436)646	7/25/95	McArthur et al.						
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		• AL	2336778	7/1977	Frence						
<u> </u>		-AM	56-12521	-2/1981-	Kobayashi, Japan — — — —					-	
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				OTHER REI	FERENCES (including Author, Title, Date, Pe	ertinent Pages, Etc.)	_				
		-AR	Application Chade Temper	enthura Seamer, Wallow Electrical Manufacturing Company Catalog. pp. 775-772, 1932/1982.							
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		AT Temperature Metallogs for CD Operal in DISM Lithography, Leffrey Backer, and Wayne Benker, pp. 111-112, 114, 116, 00/17/07.									
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	AE				et al.; Amendment filed 12/18/00, CPA fil		ed-3/3/00, Amen	dment filed 8/	23/00;			
V.C			Original Application for	ार्थ <i>स्थाप</i> के स्था	ing Claims							
	ς AF	,	Advertisement for Prot	e Technology: y	www.idinet.com: Interconnect_Devices, Inc	., 1 page; 3/6/98						
	AG		Good Things Come in	Small BGA/CSP	Paokages; www.johnstech.com/4/handboo	rk/page0 html 1 page; 3/5/	28~					
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	AH		Product Description to	Product Description for Double Ended Probes. B1052 Series; www.testprobe.com/products/b1052.html; Rika Denshi America, Inc.; 1-page, 2/4/98.								
	Al		Product Description for Test Centers, RM-500 Series Probes, www.testprobe.com/products/rm500.html. Riks Denshi America, Inc.; 1 page; 2/4/98.									
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	ΑJ		Product-Description fo	Cost Effective	Interconnections for High I/O Products; _ <u>w</u>	ww.testprobe.com/product	s/io.htm#b1303;	Rika Denshi A	merica Inc			
			1- <del>page; 2/4/98.</del>									
	<u>AK</u>		Product Description for Ball Grid Probe B1303 C3; www.testprobe.com/products/io.htm#b1303; Rike Denshi-America, Inc.; 1 page; 2/4/98.									
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		5,612,574	3/18/97	- Summarfelt et el	del			<b>-</b>			
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